

Application Data Sheet**Applicant Information**

Applicant Authority type::	Inventor
Primary Citizenship Country::	Japan
Status::	Full Capacity
Given Name::	Shuichi
Family Name::	OKAWA
City of Residence::	Tokyo
Country of Residence::	JAPAN

Applicant Authority Type::	Inventor
Primary Citizenship Country::	Japan
Status::	Full Capacity
Given Name::	Kazuhiro
Family Name::	HATTORI
City of Residence::	Tokyo
Country of Residence::	JAPAN

Correspondence Information

Correspondence Customer Number::	25944
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Application Information

Application Type::	National Phase
Subject Matter::	Utility
CD-ROM or CD-R::	None
Title::	MASK MATERIAL FOR REACTIVE ION ETCHING, MASK, AND DRY ETCHING METHOD
Attorney Docket Number::	125685
Total Drawing Sheets::	7
Small Entity::	No

Representative Information

Attorneys associated with Customer No. 25944.

Domestic Priority Information			
Application::	Continuity Type::	Parent Application::	Parent Filing Date::
This Application is a	National Stage of	PCT/JP04/008232	06/11/2004
Foreign Priority Information			
Country::	Application Number::	Filing Date::	Priority Claimed::
JAPAN	2003-188468	06/30/2003	Yes
Assignee Information			
Assignee Name::		TDK CORPORATION	
Street of mailing address::		1-13-1, Nihonbashi, Chuo-ku	
City of mailing address::		Tokyo	
Country of mailing address::		JAPAN	
Postal or Zip Code of mailing address::		103-8272	